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[Amendment under 37 CFR 1.111
Kota YOSHIKAWA

U.S. Patent Application Serial No. 09/916,314
Attorney Docket No. 010935

and Re (rhenium) and its oxide.

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IN THE CLAIMS:

Please cancel claim 1 without prejudice or disclaimer, amend claims 2 and 3, and add new claim 20, as follows:

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2. (Amended) An organic EL element comprising:
an organic EL layer formed between an anode and a cathode; and
said cathode consisting of a first conductive film that contacts to said organic EL layer and
a second conductive film that constitutes a laminated structure together with said first conductive
film, said first conductive film containing any one of an alkaline metal and an alkaline earth metal,
and
said second conductive film containing any one of at least one type metal selected from a
group consisting of Ru (ruthenium), Rh (rhodium), Ir (iridium), Os (osmium) and Re (rhenium) and
its oxide.

3. (Amended) An organic EL element comprising:
an organic EL layer formed between an anode and a cathode; and
said cathode consisting of a first conductive film that contacts to said organic EL layer and
a second conductive film that constitutes a laminated structure together with said first conductive
film, said first conductive film containing any one of an alkaline metal and an alkaline earth metal,

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and

said second conductive film formed of any one of a TiN film and a laminate film formed of a Ti film and a TiN film on said Ti film.

20. (New) An organic EL element comprising:

an organic EL layer formed between an anode and a cathode; and

said cathode consisting of a first conductive film that contacts to said organic EL layer and a second conductive film that constitutes a laminated structure together with said first conductive film, said first conductive film containing any one of an alkaline metal and an alkaline earth metal, and said second conductive film formed a laminated film consisting of conductive film containing any one of at least one type metal selected from a group consisting of Ru, Rh, Ir, Os and Re and its oxide, and any one of a TiN film and a laminate film formed of a Ti film and a TiN film on said Ti film.